

C) Amendments to the Abstract:

Kindly amend the Abstract on page 19 of the original translation as indicated hereinafter as amended in marked up version.

~~The problem of this Invention is to provide~~ The invention provides a vacuum evaporation deposition method of the winding type and a vacuum evaporation deposition apparatus of the winding type which can form a metal film on a base film made of a single layer of insulating material such as plastic film without thermal deformation, and which is superior in productivity. ~~To solve the above problem, there are arranged an~~ An electron beam irradiator 21 for irradiating irradiates an electron beam onto ~~a~~an insulating material base film 12 before deposition of metal, and a DC bias power source 22 for applying applies bias voltage between an auxiliary roller 18 for guiding the ~~material~~base film 12 with metal film deposited thereon and ~~the~~a can roller 14, whereby the ~~material~~base film 12 charged by the irradiation of the electron beam before the deposition of metal film, is made to be in close contact with the can roller 14. ~~And the material~~ The base film 12 after deposition of metal film is made to be in close contact with the can roller 14 by the bias voltage applied between the auxiliary roller 18 connected electrically to the metal film and the can roller 14.